

ABSTRACT OF THE DISCLOSURE

The optical path of exposing light is sealed in its entirety inside a chamber, pressure inside the chamber is made higher than the pressure outside the chamber and  
5 the optical characteristics of a projection optics unit are corrected in accordance with the value of pressure inside the chamber. In an exposure apparatus using exposing light having a light-emission spectral line that overlaps the absorption spectrum region of oxygen,  
10 atmospheric oxygen outside the chamber can be prevented from penetrating the optical path of the exposing light, thereby making it possible to perform exposure under oxygen-free conditions. In addition, the optimum projected image can be obtained.